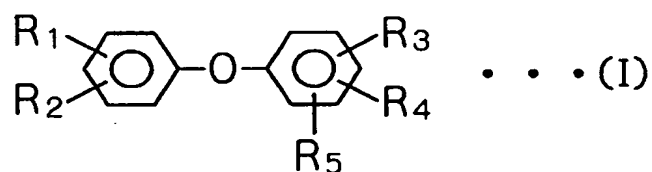


## ABSTRACT

A developer composition for resists which has a high dissolution rate (high developing sensitivity). The developer composition for resists is a developer composition for resists, comprising an organic quaternary ammonium base as a main component and a surfactant, said surfactant containing an anionic surfactant represented by the following general formula (I):



wherein at least one member of  $\text{R}_1$  and  $\text{R}_2$  represents an alkyl or alkoxy group having 5 to 18 carbon atoms and any reminder member represents a hydrogen atom, or an alkyl or alkoxy group having 5 to 18 carbon atoms, and at least onemember of  $\text{R}_3$ ,  $\text{R}_4$  and  $\text{R}_5$  represents a group represented by the following general formula (II):

[Chemical Formula 2]



wherein  $\text{M}$  represents a metal atom, and any reminder member represents a hydrogen atom or a group represented by the above general formula (II).